

PLUS Search Results for S/N 09494589, Searched November 21, 2000

5474648  
5504714  
5401350  
5578165  
6122603  
4743752  
5290037  
5092602  
5486002  
5729145  
6064308  
5973638  
5101200  
6060293  
5208854  
6018317  
5345504  
5231660  
4631708  
5694216  
5898902  
5375832  
4511843  
5747972  
5576629  
5939886  
5488631  
5483127  
4284490  
5302882  
5831550  
5195045  
5251120  
5777538  
5604352  
5748464  
5883392  
5901246  
5875108  
6081750  
5567241  
6068784  
5556501

3926556  
5600303  
5692029  
5223795  
5434509  
5432455  
5515303

Most Frequently Occurring Classifications of Patents Returned  
From A Search of 09494589 on November 21, 2000

Combined Classifications

- 6 156/345 (2 OR, 4 XR)  
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL  
MANUFACTURE  
156/345 DIFFERENTIAL ETCHING APPARATUS
- 4 324/536 (4 OR, 0 XR)  
Class 324 : ELECTRICITY: MEASURING AND TESTING  
324/500 FAULT DETECTING IN ELECTRIC CIRCUITS AND OF  
ELECTRIC COMPONENTS  
324/512 .For fault location  
324/536 ..By spark or arc discharge
- 4 473/199 (4 OR, 0 XR)  
Class 473 : GAMES USING TANGIBLE PROJECTILE  
473/131 GOLF  
473/198 .Moving projectile responsive sensor or  
indicator  
473/199 ..Electrical
- 3 315/111.21 (1 OR, 2 XR)  
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS  
  
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL  
SUPPLY TO THE DISCHARGE SPACE  
315/111.21 .Plasma generating
- 3 324/520 (0 OR, 3 XR)  
Class 324 : ELECTRICITY: MEASURING AND TESTING  
324/500 FAULT DETECTING IN ELECTRIC CIRCUITS AND OF  
ELECTRIC COMPONENTS  
324/512 .For fault location  
324/520 ..By frequency sensitive or responsive  
detection
- 3 324/613 (0 OR, 3 XR)  
Class 324 : ELECTRICITY: MEASURING AND TESTING  
324/600 IMPEDANCE, ADMITTANCE OR OTHER QUANTITIES  
REPRESENTATIVE OF ELECTRICAL STIMULUS/RESPONSE  
RELATIONSHIPS

324/612 .Parameter related to the reproduction or  
fidelity of a signal affected by a circuit under test  
324/613 ..Noise

3 361/113 (0 OR, 3 XR)

Class 361 : ELECTRICITY: ELECTRICAL SYSTEMS AND DEVICES

361/1 SAFETY AND PROTECTION OF SYSTEMS AND DEVICES  
361/113 .With tuned circuit

3 455/234.1 (0 OR, 3 XR)

Class 455 : TELECOMMUNICATIONS

455/130 RECEIVER OR ANALOG MODULATED SIGNAL FREQUENCY  
CONVERTER

455/230 .Local control of receiver operation  
455/232.1 ..Gain control  
455/234.1 ...Automatic

2 118/723I (0 OR, 2 XR)

Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION  
118/722 .With treating means (e.g., jarring)  
118/723R ..By creating electric field (e.g., gas  
activation, plasma, etc.)  
118/723I ...Radio frequency antenna or radio frequency  
inductive coil discharge means

2 204/192.12 (0 OR, 2 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/192.1 .Coating, forming or etching by sputtering  
204/192.12 ..Glow discharge sputter deposition (e.g.,  
cathode sputtering, etc.)

2 204/298.08 (1 OR, 1 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/193 APPARATUS  
204/298.01 .Coating, forming or etching by sputtering  
204/298.02 ..Coating  
204/298.08 ...Specified power supply or matching network

2 204/298.34 (0 OR, 2 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/193 APPARATUS  
204/298.01 .Coating, forming or etching by sputtering

204/298.31 ..Etching  
204/298.34 ...Auxiliary electrode, bias means or specified  
power supply

2 204/298.38 (0 OR, 2 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/193 APPARATUS

204/298.01 .Coating, forming or etching by sputtering

204/298.31 ..Etching

204/298.38 ...Microwave excitation

2 216/61 (0 OR, 2 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/58 GAS PHASE ETCHING OF SUBSTRATE

216/59 .With measuring, testing, or inspecting

216/61 ..By electrical means or of an electrical  
property

2 216/67 (0 OR, 2 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/58 GAS PHASE ETCHING OF SUBSTRATE

216/63 .Application of energy to the gaseous etchant  
or to the substrate being etched

216/67 ..Using plasma

2 216/68 (2 OR, 0 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/58 GAS PHASE ETCHING OF SUBSTRATE

216/63 .Application of energy to the gaseous etchant  
or to the substrate being etched

216/67 ..Using plasma

216/68 ...Using coil to generate the plasma

2 250/492.3 (2 OR, 0 XR)

Class 250 : RADIANT ENERGY

250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

250/492.3 .Ion or electron beam irradiation

2 336/173 (1 OR, 1 XR)

Class 336 : INDUCTOR DEVICES

336/173 INTERLINKED COILS OR WINDINGS (E.G., CURRENT  
TRANSFORMER)

2 340/870.02 (0 OR, 2 XR)

Class 340 : COMMUNICATIONS: ELECTRICAL

340/870.01 CONTINUOUSLY VARIABLE INDICATING (E.G.,  
TELEMETERING)

340/870.02 .With meter reading

2 380/205 (2 OR, 0 XR)

Class 380 : CRYPTOGRAPHY

380/200 VIDEO CRYPTOGRAPHY

380/205 .Video electric signal masking

2 438/17 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/14 WITH MEASURING OR TESTING

438/17 .Electrical characteristic sensed

2 455/233.1 (0 OR, 2 XR)

Class 455 : TELECOMMUNICATIONS

455/130 RECEIVER OR ANALOG MODULATED SIGNAL FREQUENCY  
CONVERTER

455/230 .Local control of receiver operation

455/232.1 ..Gain control

455/233.1 ...With diverse control (tone, etc.)

2 455/240.1 (0 OR, 2 XR)

Class 455 : TELECOMMUNICATIONS

455/130 RECEIVER OR ANALOG MODULATED SIGNAL FREQUENCY  
CONVERTER

455/230 .Local control of receiver operation

455/232.1 ..Gain control

455/234.1 ...Automatic

455/239.1 ....Nonlinear automatic gain control

455/240.1 .....Variable automatic gain control loop gain

2 700/17 (2 OR, 0 XR)

Class 700 : DATA PROCESSING: GENERIC CONTROL SYSTEMS OR  
SPECIFIC APPLICATIONS

700/1 GENERIC CONTROL SYSTEM, APPARATUS OR PROCESS

700/11 .Sequential or selective

700/17 ..Operator interface (e.g., display with  
control)

2 700/83 (0 OR, 2 XR)

Class 700 : DATA PROCESSING: GENERIC CONTROL SYSTEMS OR  
SPECIFIC APPLICATIONS

700/1            GENERIC CONTROL SYSTEM, APPARATUS OR PROCESS  
700/83           .Having operator control interface (e.g.,  
                 control/display console)